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(54) Title: PLASTIC LENS AND MANUFACTURING METHOD OF PLASTIC LENS

(57) Abstract: A plastic lens includes: a plastic lens base material; a hard coat layer formed on the plastic lens base material; an organic antireflection film formed on the hard coat layer; and a primer layer between the plastic lens base material and the hard coat layer. The plastic lens base material contains at least a sulfur atom. The hard coat layer contains at least: fine metal oxide particles containing a titanium oxide having a rutile-type crystalline structure; and an organosilicon compound represented by a general formula of $R^1SiX^1_3$. The antireflection film contains a coating composition containing at least: an organosilicon compound represented by a general formula of $X_mR^2_{3-m}Si\text{-}Y\text{-}SiR^2_{3-m}X_m$; an epoxy group-containing organic compound containing one or more epoxy group in a molecule; and fine silica particles with average particle size of 1 to 150 nm, the antireflection film having a refractive index lower than that of the hard coat layer by 0.10 or more.

WO 2007/043301 A1